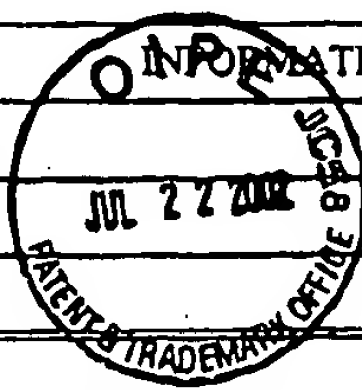


QUERY CONTROL FORM		RTIS USE ONLY	
Application No.	09/925,102	Prepared by	NH
Examiner-GAU	Dang - 2818	Date	1-29-04
		No. of queries	1
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		Tracking Number	05888489
		Week Date	01/12/04

JACKET			
a. Serial No.	f. Foreign Priority	k. Print Claim(s)	p. PTO-1449
b. Applicant(s)	g. Disclaimer	l. Print Fig.	q. PTOL-85b
c. Continuing Data	h. Microfiche Appendix	m. Searched Column	r. Abstract
d. PCT	i. Title	n. PTO-270/328	s. Sheets/Figs
e. Domestic Priority	j. Claims Allowed	o. PTO-892	t. Other

SPECIFICATION	MESSAGE
a. Page Missing	PTO-1449: Please either initial or line through citations. Copy provided for reference.
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g. Brief Description	
h. Sequence Listing	
i. Appendix	
j. Amendments	
k. Other	
CLAIMS	
a. Claim(s) Missing	
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k. Other	

U.S. Department of Commerce, Patent and Trademark Office				Atty Docket No.		Serial N	
				M-11822 US		09/925,102	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicant(s)		RECEIVED	
(Use several sheets if necessary)				Jack H. Yuan et al.		JUL 30 2002	
				Filing Date		GROUP Technology Center 2100	
				August 8, 2001		2185	
U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
PD	AP	6,151,248	Nov. 21, 2000	Harari et al.			
PD	AQ	6,222,762	Apr. 24, 2001	Guterman et al.			
Foreign Patent Documents							
							Translation
		Document	Date	Country	Class	Subclass	Yes No
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
PD	AR -	Nozaki et al., "A 1-Mb EEPROM with MONOS Memory Cell for Semiconductor Disk Application," <i>IEEE Journal of Solid State Circuits</i> , Vol. 26, No. 4, April 1991, pp. 497-501.					
PD	AS -	Eitan et al., "NROM: A Novel Localized Trapping, 2-Bit Nonvolatile Memory Cell," <i>IEEE Electron Device Letters</i> , Vol. 21, No. 11, November 2000, pp. 543-545.					
PD	AT	DiMaria et al., "Electrically-alterable read-only-memory using Si-rich SiO <sub>2</sub> injectors and a floating polycrystalline silicon storage layer," <i>J. Appl. Phys.</i> 52(7), July 1981, pp. 4825-4842.					
PD	AU	Hori et al., "A MOSFET with Si-implanted Gate-SiO <sub>2</sub> Insulator for Nonvolatile Memory Applications," <i>IEDM 92</i> , April 1992, pp. 469-472.					
Examiner		PHUC T. DANG		Date Considered		4/1/04	
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.							

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					M-11822 US		09/925,102	
					Applicant(s)			
					Jack H. Yuan et al.			
					Filing Date		Group	
					August 8, 2001		2185	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
PD	AA	5,043,940	Aug. 27, 1991	Harari			<b>RECEIVED</b> <b>JUL 30 2002</b> <b>Technology Center 2100</b>	
	AB	5,070,032	Dec. 3, 1991	Yuan et al.				
	AC	5,095,344	Mar. 10, 1992	Harari				
	AD	5,172,338	Dec. 15, 1992	Mehrotra et al.				
	AE	5,297,148	Mar. 22, 1994	Harari et al.				
	AF	5,313,421	May 17, 1994	Guterman et al.				
	AG	5,315,541	May 24, 1994	Harari et al.				
	AH	5,343,063	Aug. 30, 1994	Yuan et al.				
	AI	5,661,053	Aug. 26, 1997	Yuan				
	AJ	5,712,180	Jan. 27, 1998	Guterman et al.				
PD	AK	6,103,573	Aug. 15, 2000	Harari et al.				
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
PD	AL	Aritome, Seiichi, "Advanced Flash Memory Technology and Trends for File Storage Application," IEDM Technical Digest, International Electronic Devices Meeting, IEEE, San Francisco, California, December 10-13, 2000, pp 33.1.1-33.1.4.						
PD	AM	Takeuchi, Y., et al., "A Self-Aligned STI Process Integration for Low Cost and Highly Reliable 1Gbit Flash Memories," 1998 Symposium on VLSI Technology; Digest of Technical Papers, IEEE, Honolulu, Hawaii, June 9-11, 1998, pp. 102-103.						
PD	AN	Lee, Jae-Duk, et al., "Effects of Parasitic Capacitance on NAND Flash Memory Cell Operation," Non-Volatile Semiconductor Memory Workshop, IEEE, Monterey, California, August 12-16, 2001, pp. 90-92.						
PD	AO	Chan, et al., "A True Single-Transistor Oxide-Nitride-Oxide EEPROM Device," IEEE Electron Device Letters, Vol. EDL-8, No. 3, March 1987, pp. 93-95.						
Examiner		PHUC T. DANG		Date Considered		4/11/04		
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								

## INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Atty. Docket No.

C000400

Serial No.

09/950,959

Applicant

Robert L. Dickerman et al.

Filing Date

September 12, 2003

Group

2858

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
PD	4,914,378	4/90	Hayashi et al.			
PD	4,656,595	4/87	Hognestad			

## FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	WO 01/94876	12/01	WIPO				
PD	0 277 467	10/88	EP				

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Page, Etc.)

PD		PCT International Search Report dated 24/10/2003
PD		Horowitz P and Hill W.: "The Art of Electronics" Cambridge University Press, Cambridge, XP002246138, ISBN: 0-521-37095-7 - See argumentation against the unity of the application - Page 223 - Page 224

EXAMINER

PHUC T. DANG

DATE CONSIDERED

4/1/04

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